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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 1 Of

Complete If Known				
Application Number	10/849,345			
Filing Date	May 19, 2004			
First Named Inventor	Robert H. Burgener, II			
Group Art Unit	2811			
Examiner Name	Thien F. Tran			
Attorney Docket Number	3398.2.9			

	NON PATENT LITERATURE DOCUMENTS			
Examiner Initials *	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, a No.¹ serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.		
TT	.01	AULBUR, W.; Density Functional Theory: Basic Ideas & Applications; Ohio State University.		
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11	О3	ZUNGER, A.; Practical Doping Principles; NCPV and Solar Program Review Meeting 2003; pp. 831-835.		
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Examiner Signature Win MW	Date Considered	02-27- 2006
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Substitute for form 14498/PTO Complete if Known Application Number 10/849,345 INFORMATION DISCLOSURE Filing Date May 19, 2004 STATEMENT BY APPLICANT Robert H. Burgener, II First Named Inventor **Group Art Unit** 2811 (use as many sheets as necessary) **Examiner Name** Thien F. Tran 3398.2.9 **Attorney Docket Number** Of Sheet

015	WILKINSON, J., XIONG, G., UCER, K.B., and WILLIAMS, R.T.; Lifetime and Oscillator Strength of Excitonic Luminescence in Zinc Oxide; Department of Physics, Wake Forest University, Winston-Salem, NC.	
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			CLOSURE	Filing Date	May 19, 2004	
STATEMENT BY APPLICANT				First Named Inventor	Robert H. Burgener, II	
				Group Art Unit	2811	
(use as many sheets as necessary)		Examiner Name	Thien F. Tran			
Sheet	3	Of	9	Attorney Docket Number	3398.2.9	

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(use as many sheets as necessary)	Examiner Name	Thien F. Tran
Sheet 6 Of 9	Attorney Docket Number	3398.2.9

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	Examiner Signature	Thien Jane	Date Considered	02-27-2006
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Substitute for form 1449B/PTO Complete if Known **Application Number** 10/849,345 INFORMATION DISCLOSURE Filing Date May 19, 2004 STATEMENT BY APPLICANT First Named Inventor Robert H. Burgener, II Group Art Unit 2811 (use as many sheets as necessary) Thien F. Tran **Examiner Name** 3398.2.9 Of Attorney Docket Number Sheet 7

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Examiner Signature	Thien,	SAL .	Date Considered	02-27-2006	

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Substitute for form 1449B/PTO		Complete if Known
	Application Number	10/849,345
Information disclosure	Filing Date	May 19, 2004
STATEMENT BY APPLICANT	First Named Inventor	Robert H. Burgener, II
	Group Art Unit	2811
(use as many sheets as necessary)	Examiner Name	Thien F. Tran
Sheet 8 Of 9	Attorney Docket Number	3398.2.9

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Examiner Signature	Thien Sour	Date Considered	02-27-2006	
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¹ Applicant's unique citation designation number (optional) . ² Applicant is to place a check mark here if English language Translation is attached.

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Substitut	e for form 1449i	В/РТО		Complete if Known			
				Application Number	10/849,345		
INFC	PRMATIC	ON DISCLO	SURE	Filing Date	May 19, 2004		
STA	STATEMENT BY APPLICANT			First Named Inventor	Robert H. Burgener, II		
				Group Art Unit	2811		
	(use as many	sheets as necessar	y)	Examiner Name	Thien F. Tran		
Sheet	9	Of	9	Attorney Docket Number	3398.2.9		

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Examiner Signature	Thien both	Date Considered	02-27-2006

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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1 Of 1

Complete if Known					
Application Number	10/849,345				
Filing Date	May 19, 2004				
First Named Inventor	Robert H. Burgener, II				
Group Art Unit	2811				
Examiner Name	Thien F. Tran				
Attorney Docket Number	3398.2.9				

			U.S. PATENT	DOCUMENTS	
Examiner Initials *	Cite No.1	Document Number	Publication Date	Name of Patentee or Applicant of	Pages, Columns, Lines, Where Relevan
		Number - Kind Code ^{2 (f known)}	MM-DD-YYYY	Cited Document	Passages or Relevant Figures Appear
TT_	U1	US-6,838,308 B2	01/2005	Haga, Koichi	
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	U5				
	U6				
	U7				
	U8				
	U9				
	U10				
	U11				
	U12				
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	FOREIGN PATENT DOCUMENTS							
Examiner Initials*	Cite No.1	Foreign Patent Document	Publication Date	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	7⁰		
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Complete if Known

Application Number 10/849,345

Filing Date May 19, 2004

First Named Inventor Robert H. Burgener, II

Group Art Unit 2811

Examiner Name Thien F. Tran

Attorney Docket Number 3398.2.9

(use as many sheets as necessary) .

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Sheet 1 Of 1

			U.S. PATENT	DOCUMENTS		
Examiner Initials *	Cita Na 1	Document Number Publication Date		Name of Patentee or Applicant of	Pages, Columns, Lines, Where Relevant	
	Cite No.'	Number - Kind Code ^{2 (f known)}	MM-DD-YYYY	Cited Document	Passages or Relevant Figures Appear	
ŢŢ	U1	US-3,664,867-B1	05/23/1972	Galli et al.		
TT	U2	US-4,399,441-B1	08/16/1983	Vaughn et al.		

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No.1	Foreign Patent Document	Publication Date	Name of Patentee or Applicant of Cited	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	
		Country Code ³ - Number ⁴ - Kind Code ⁶ (Fancum)	MM-DD-YYYY	Document		T ⁰
TI	F1	EP - 1219731-A1	07/03/2002	Yoshida, et al.		
TT	F2	JP 2002-68890-A!	03/08/2002	Ogata, et al.		

١	Examiner Signature	linen	JEML .	Date Considered	2-27-200G	

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